

What is claimed is:

1. A condensate polisher system comprising:

 a feed water flow;

 at least one deep bed polisher, wherein said deep bed polisher comprises resin beads that are substantially exclusively single ion type, wherein said feed water enters said at least one deep bed polisher to produce a semi-purified water flow;

 at least one powdered resin polisher, wherein said powdered resin polisher comprises a mixed ion powdered resin;

 wherein said at least one powdered resin polisher accepts said semi-purified water flow from said at least one deep bed polisher to produce a purified water flow.
2. The system of claim 1, wherein said resins beads are cation type.
3. The system of claim 1, wherein the ratio of cation to anion powder in said mixed ion powdered resin is from 1:1 to 1:10 by weight.
4. The system of claim 3, wherein the ratio of cation to anion powder in said mixed ion powdered resin is 1:3.
5. The system of claim 1, wherein said feed water flow is adjusted to approximately pH 7.
6. The system of claim 1, wherein the number of powdered resin polishers in said condensate polisher system is greater than the number of deep bed polishers.
7. The system of claim 6, wherein said semi-purified water flow is directed to different powdered resin polishers depending on the nature of the semi-purified water flow.

8. The system of claim 1, wherein said resins beads and said powdered resin comprises polystyrene.
9. The system of claim 1, wherein said resin powder comprises particulates approximately 25 micrometers in size.
10. The system of claim 1, wherein said resin beads are from about 500-1000 micrometers in diameter.
11. A condensate polisher system comprising:
a feed water flow;
at least one deep bed polisher, wherein said deep bed polisher comprises resin beads that are substantially exclusively single ion type, wherein said feed water enters said at least one deep bed polisher to produce semi-purified water;
at least one powdered resin polisher, wherein said powdered resin polisher comprises powdered resin is substantially exclusively single ion type opposite to said resin beads;
wherein said at least one powdered resin polisher accepts said semi-purified water flow from said at least one deep bed polisher to produce a purified water flow.
12. The system of claim 11, wherein said resins beads are cation type.
13. The system of claim 11, wherein the number of powdered resin polishers in said condensate polisher system is greater than the number of deep bed polishers.
14. The system of claim 11, wherein said resins beads and said powdered resin comprises polystyrene.

15. A condensate polisher system comprising:
- a feed water flow;
 - at least one deep bed polisher, wherein said deep bed polisher comprises charged resin beads that are substantially exclusively cation type, wherein said feed water enters said at least one deep bed polisher to produce a semi-purified water flow;
 - at least one powdered resin polisher, wherein said powdered resin polisher comprises a mixed ion powdered resin;
 - wherein said at least one powdered resin polisher accepts said semi-purified water flow from said at least one deep bed polisher to produce a purified water flow.
16. The system of claim 15, wherein the ratio of cation to anion powder in said mixed ion powdered resin is from 1:1 to 1:10 by weight.
17. The system of claim 16, wherein the ratio of cation to anion powder in said mixed ion powdered resin is 1:3.
18. The system of claim 15, wherein the number of powdered resin polishers in said condensate polisher system is greater than the number of deep bed polishers.
19. The system of claim 15, wherein said resins beads and said powdered resin comprises polystyrene.
20. The system of claim 19, wherein said polystyrene comprises the cation exchange functional group of sulfonate and the anion exchange functional group of amine.